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## Formation of Alkylsiloxane Self-Assembled Monolayers (SAMs) on SiO<sub>2</sub> and TiO<sub>2</sub> in Vacuum

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Self-assembled monolayers (SAMs) are thin organic films which form spontaneously on solid surfaces. They have been shown to be useful as passivating layers and also for the modification of surface properties. Potential applications include wetting, adhesion, friction, chemical sensing, ultrafine scale lithography, and protection of metals against corrosion. SAMs of Alkyltrichlorosilane were formed on SiO<sub>2</sub> and TiO<sub>2</sub> surface from a gas phase. Several different varieties of SAMs have been investigated, including Alkyltrichlorosilanes(CH<sub>3</sub>(CH<sub>2</sub>)<sub>n</sub>-1-SiCl<sub>3</sub>) on SiO<sub>2</sub> and TiO<sub>2</sub>. Alkyltrichlorosilane-based SAMs formed on SiO<sub>2</sub> and TiO<sub>2</sub> have been studied using X-ray photoelectron spectroscopy(XPS) and Atomic Force Microscopy(AFM) and contact angle analysis.

The Alkyltrichlorosilane-based SAMs are more efficiently and well formed on the TiO<sub>2</sub> surface as compared to those on the SiO<sub>2</sub>.